

ABSTRACT

FILM-THICKNESS MEASURING APPARATUS, FILM-THICKNESS MEASURING METHOD, AND 5 POLISHING APPARATUS HAVING THE FILM-THICKNESS MEASURING APPARATUS

A film-thickness measuring apparatus and a film-thickness measuring method capable of improving an accuracy of the film-thickness measurement are disclosed. The
10 film-thickness measuring apparatus includes a substrate stage configured to support a substrate horizontally, a rinsing water supply structure configured to supply rinsing water onto an entire surface of the substrate on the substrate stage, a film-thickness measuring head configured to transmit light to a measurement area of the surface of the substrate on the substrate stage, produce a spectrum of reflected light from the measurement area, and
15 determine a film thickness of the substrate from the spectrum, and a fluid supply structure configured to form a flow of a gas on a path of the light and supply the flow of the gas onto the measurement area.

FIG. 6A